Electronic Supplementary Information

Aromatic Hydroxylation of Anthracene Derivatives by a Chromium(III)-Superoxo Complex *via* Proton-Coupled Electron Transfer

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Experimental Section

Materials. All chemicals, which were of reagent-grade quality, were obtained commercially and used without further purification, unless otherwise noted. Solvents were dried according to published procedures and distilled under an Ar atmosphere prior to use.^{S1} Anthracene and its derivatives, such as 9-methylanthracne, 9-bromoanthracene, 9-anthracenecarboxaldehyde and 9,10-dimethylanthracene, were purchased from Aldrich Chemical Co. and used as received. Trifluromethanesulfonic acid (triflic acid; CF₃SO₃H; HOTf) was purchased from Tokyo Chemical Industry Co., LTD. The deuterated anthracene compound (anthracene-*d*¹⁰) was also purchased from Aldrich Chemical Co. and used as received. ¹⁸O₂ gas (98% ¹⁸O-enriched) was purchased from ICON Services Inc. (Summit, NJ. USA). The chromium complexes, [(TMC)Cr^{II}(Cl)]Cl, [(TMC)Cr^{III}(O₂⁻)(Cl)]Cl (1), and [(TMC)Cr^{III}(¹⁸O₂⁻)(Cl)]Cl (1-¹⁸O), were synthesized according to the literature methods.^{S2, S3}

Instrumentation. UV-vis spectra were recorded on a Hewlett Packard 8453 diode array spectrophotometer equipped with a UNISOKU Scientific Instruments Cryostat USP-203A for low-temperature experiments or on a UNISOKU RSP-601 stopped-flow spectrometer equipped with a MOS-type highly sensitive photodiode-array. Cold spray ionization mass (CSI-MS) spectra were collected on a JMS-T100CS (JEOL) mass spectrometer equipped with a CSI source [conditions: needle voltage = 2.2 kV, orifice 1 current = 50 - 500 nA, orifice 1 voltage = 0 - 20 V, ringlens voltage = 10 V, ion source temperature = 5° C, spray temperature = -40° C]. X-band CW-EPR spectra were recorded at 5 K using an X-band Bruker EMX-plus spectrometer equipped with a dual mode cavity (ER 4116DM) [experimental parameters: microwave frequency = 9.647 GHz, microwave power = 1.0 mW, modulation amplitude = 10 G, gain = 1×10^{4} , modulation frequency = 100 kHz, time constant = 40.96 ms, conversion time = 81.00 ms]. Product analysis was performed by ¹H NMR measurements on a Bruker model digital AVANCE III 400 FT-NMR spectrometer. Product analysis was also performed with Thermo Finnigan (Austin, Texas, USA) FOCUS DSQ (dual stage quadrupole) mass spectrometer interfaced with Finnigan FOCUS gas chromatograph (GC-MS).

Kinetic Measurements. Typically, kinetic measurements for the oxidation of anthracene and its derivatives, such as 9-substituted anthracene derivatives (XAn: 9-methylanthracene, 9-bromoanthracene and 9-anthracenecarboxaldehyde) and 9,10-dimethylanthracene, by $[(TMC)Cr^{III}(O_2^{-})]^{2+}$ (1) in the presence of HOTf (2.5 mM) were performed on a UNISOKU RSP-601 stopped-flow spectrometer in MeCN at 233 K under the conditions such that [1] = [substrate]. Rates of oxidation of anthracene and 9-substituted anthracene derivatives (XAn) by 1 were monitored by following the decay of the absorption band at 550 nm due to 1 in the presence of HOTf (2.5 mM) in MeCN at 233 K. The second-order rate constants (k_{ox}) for 6-electron oxidation of anthracene, 4-electron oxidation of XAn, and 2-electron

oxidation of 9,10-dimethylanthracene by **1** (3-electron oxidant) in the presence of HOTf (2.5 mM) in MeCN at 233 K were determined using eqn (5) in text, eqn (S5) and eqn (S10) in ESI, respectively.

Determination of k_{ox} value for the four-electron oxidation of substrate by 3-electron oxidant.



$$rate = -d[Cr^{III}(O_2)]/dt = k_{ox}[Cr^{III}(O_2)][XAn]$$
(S1)

$$[Cr^{III}(O_2)]_0 = [Cr^{III}(O_2)] + [Cr^{III}]$$
(S2)

$$[XAn]_0 = [XAn] + (4/3)[Cr^{III}]$$
(S3)

Thus,
$$-d[Cr^{III}(O_2)]/dt = k_{ox}[Cr^{III}(O_2)]([XAn]_0 - (4/3)[Cr^{III}(O_2)]_0 + (4/3)[Cr^{III}(O_2)])$$
 (S4)

Solving the differential eqn (S4) with eqns. (S2) and (S3) gives eqn (S5),

$$\log [x/(C + (4/3)x)] = -(C/2.3)k_{ox}t + \log [x_0/(C + (4/3)x_0)]$$
(S5)

where $x = [Cr^{III}(O_2)]$, $x_0 = [Cr^{III}(O_2)]_0$, $C = [XAn]_0 - (4/3)[Cr^{III}(O_2)]_0$, $x_0/(C + (4/3)x_0) = 1$. Thus, plot of log[x/(C + (4/3)x)] *vs. t* gives a straight line that passes through zero with slope = $-(C/2.3)k_{ox}$, where C is $-(1/3)x_0$.

Determination of k_{ox} value for the two-electron oxidation of substrate by 3-electron oxidant.



$$rate = -d[Cr^{III}(O_2)]/dt = k_{ox}[Cr^{III}(O_2)][Me_2An]$$
(S6)

$$[Cr^{III}(O_2)]_0 = [Cr^{III}(O_2)] + [Cr^{III}]$$
(S7)

$$[Me_2An]_0 = [Me_2An] + (2/3)[Cr^{III}]$$
(S8)

Thus,
$$-d[Cr^{III}(O_2)]/dt = k_{ox}[Cr^{III}(O_2)]([Me_2An]_0 - (2/3)[Cr^{III}(O_2)]_0 + (2/3)[Cr^{III}(O_2)])$$
 (S9)

Solving the differential eqn (S9) with eqns (S7) and (S8) gives eqn (S10),

$$\log[x/(C + (2/3)x)] = -(C/2.3)k_{ox}t + \log[x_0/(C + (2/3)x_0)]$$
(S10)

where $x = [Cr^{III}(O_2)]$, $x_0 = [Cr^{III}(O_2)]_0$, $C = [Me_2An]_0 - (2/3)[Cr^{III}(O_2)]_0$, $x_0/(C + (2/3)x_0) = 1$. Thus, plot of log[x/(C + (2/3)x)] *vs. t* gives a straight line that passes through zero with slope $= -(C/2.3)k_{ox}$, where C is $(1/3)x_0$.

References

- S1 W. L. F. Armarego, C. L. L. Chai, in *Purification of Laboratory Chemicals*, 6th ed., Pergamon Press, Oxford, 2009.
- S2 J. Cho, J. Woo and W. Nam, J. Am. Chem. Soc., 2010, **132**, 5958.
- S3 J. Cho, J. Woo and W. Nam, J. Am. Chem. Soc., 2012, **134**, 11112.

[HOTf], mM	$k_{ m ox},{ m M}^{-1}{ m s}^{-1}$
2.5	$4.1(4) \times 10$
5.0	$1.0(1) \times 10^2$
7.5	$2.3(2) \times 10^2$
10.0	$4.6(3) \times 10^2$

Table S1 Second-order rate constants (k_{ox}) determined in the oxidation of anthracene by **1** in the presence of various concentrations of HOTf in MeCN at 233 K.

Table S2 Second-order rate constants (k_{ox}) determined in the oxidation of anthracene and its derivativesby 1 in the presence of HOTf (2.50 mM) in MeCN at 233 K

Substrate	Eox, V vs. SCE	$k_{\mathrm{ox}},\mathrm{M}^{-1}\mathrm{s}^{-1}$
9,10-dimethylanthracene	1.05 ^a	$4.8(4) \times 10^2$
9-methylanthracene	1.11 ^a	$1.3(1) \times 10^{2}$
anthracene	1.19 ^a	4.1(4) × 10
9-bromoanthracene	1.30 ^a	3.3(3) × 10
9-anthracenecarboxaldehyde	1.37 ^b	5.0(4)

^aTaken from the reference: S. Fukuzumi, K. Okhubo and T. Okamoto, *J. Am. Chem. Soc.*, 2002, **124**, 14147. ^bTaken from the reference: S. Okazaki, M. Oyama and S. Nomura, *Electroanalysis*, 1997, **9**, 1242.



Fig. S1 UV-vis spectra of **1** (1.0 mM) in the absence (red line) and presence (black line) of anthracene (1.0 mM) in MeCN at 233 K. No reaction between **1** and anthracene was observed.



Fig. S2 Titration for the disappearance of **1** (red circles) as a function of the concentration of anthracene (0 - 1.0 mM) added to the solution of **1** (1.0 mM) in increments of 0.10 mM in the presence of HOTf (1.0 mM) in MeCN at 233 K.



Fig. S3 ¹H NMR spectra of (a) anthracene (10 mM) and (b) anthraquinone (10 mM) as the authentic references, and (c) the reaction products obtained in the oxidation of anthracene (1.0 mM) by **1** (2.0 mM) in the presence of HOTf (2.0 mM) in MeCN- d_3 at 233 K.



Fig. S4 GC-MS spectra of (a) anthraquinone (1.0 mM) as an authentic reference and (b, c) the reaction solutions obtained in the oxidation of anthracene (0.50 mM) by (b) $1^{-16}O_2$ (1.0 mM) and (c) $1^{-18}O_2$ (1.0 mM) in the presence of HOTf (1.0 mM) in MeCN at 233 K. The percentage of ¹⁸O in anthraquinone product in (c) was determined to be 94(4)% by comparison of the relative abundances at m/z = 212 for anthraquinone-¹⁸O,¹⁸O, m/z = 210 for anthraquinone-¹⁶O,¹⁸O and m/z = 208 for anthraquinone-¹⁶O,¹⁶O.



Fig. S5 (a) CSI-MS spectrum of the complete reaction solution obtained in the oxidation of anthracene (0.50 mM) by **1** (1.0 mM) in the presence of HOTf (1.0 mM) in MeCN at 233 K. The peak at m/z = 378.2 corresponds to $[Cr^{III}(TMC)(Cl_2)]^+$ (*calc.* m/z = 378.1). Inset shows the isotope distribution pattern of the peak at m/z = 378.2. (b) X-band EPR spectrum of the complete reaction solution obtained in the oxidation of anthracene (0.50 mM) by **1** (1.0 mM) in the presence of HOTf (1.0 mM) in MeCN at 233 K. The spectrum was recorded at 5 K.



Fig. S6 Plots of $\log[x/(C + 2x)]$ *vs.* time for the oxidation of anthracene- h_{10} (0.50 mM; red circles) and anthracene- d_{10} (0.50 mM; blue circles) by **1** (0.50 mM) in the presence of HOTf (2.5 mM) in MeCN at 233 K. The k_{ox} values were determined by using $\log[x/(C + 2x)] = -(C/2.3)k_{ox}t + \log[x_0/(C + 2x_0)]$, where $x = [\mathbf{1}], x_0 = [\mathbf{1}]_0, C = -x_0 = -[\mathbf{1}]_0$ and $x_0/(C + 2x_0) = 1$ [eqn (5) in text].



Fig. S7 UV-visible spectral changes observed in the oxidation of anthracene (0.50 mM) by **1** (0.50 mM) in the presence of HOTf (10 mM) in MeCN at 233 K. Inset shows the time profiles at 550 nm due to decay of **1** (0.50 mM) in the oxidation of anthracene (0.50 mM) by **1** in the presence of HOTf [2.5 mM (black), 5.0 mM (red), 7.5 mM (green) and 10 mM, (blue)] in MeCN at 233 K.



Fig. S8 Plots of $\log[x/(C+2x)]$ *vs.* time for the oxidation of anthracene (0.50 mM) by **1** (0.50 mM) in the presence of HOTf [(a) 2.5 mM, (b) 5.0 mM, (c) 7.5 mM and (d) 10 mM] in MeCN at 233 K. The k_{ox} values were determined by using $\log[x/(C+2x)] = -(C/2.3)k_{ox}t + \log[x_0/(C+2x_0)]$, where x = [1], $x_0 = [1]_0$, $C = -[1]_0$ and $x_0/(C+2x_0) = 1$ [eqn (5) in text].



Fig. S9 UV-vis spectral changes observed in the oxidation of anthracene (0.50 mM) by $[Cr^{IV}(TMC)(O)]^{2+}$ (1.0 mM) in the presence of HOTf (2.5 mM) in MeCN at 233 K. The inset shows the time profile monitored at 605 nm due to the decay of $[Cr^{IV}(TMC)(O)]^{2+}$.



Fig. S10 Plots of $\log[x/(C + (4/3)x)]$ *vs.* time for the oxidation of (a) 9-methylanthracene (0.50 mM), (b) 9-bromoanthracene (0.50 mM) and (c) 9-anthracenecarboxaldehyde (0.50 mM) by **1** (0.50 mM) in the presence of HOTf (2.5 mM) in MeCN at 233 K. The k_{ox} values were determined by using $\log[x/(C + (4/3)x)] = -(C/2.3)k_{ox}t + \log [x_0/(C + (4/3)x_0)]$, where $x = [\mathbf{1}]$, $x_0 = [\mathbf{1}]_0$, $C = [XAn]_0 - (4/3)[\mathbf{1}]_0 = -1/3[\mathbf{1}]_0$ and $x_0/(C + (4/3)x_0) = 1$ [eqn (S5) in ESI].



Fig. S11 Plot of $\log[x/(C + (2/3)x)]$ *vs.* time for the oxidation of 9,10-dimethylanthracene (0.50 mM) by 1 (0.50 mM) in the presence of HOTf (2.5 mM) in MeCN at 233 K. The k_{ox} values were determined by using $\log[x/(C + (2/3)x)] = -(C/2.3)k_{ox}t + \log[x_0/(C + (2/3)x_0)]$, where x = [1], $x_0 = [1]_0$, $C = [XAn]_0 - (2/3)[1]_0 = 1/3[1]_0$ and $x_0/(C + (2/3)x_0) = 1$ [eqn (S10) in ESI].